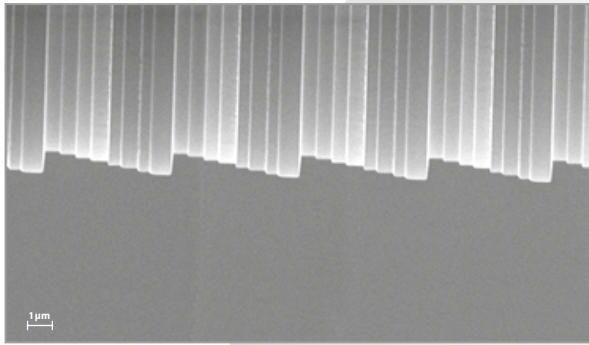
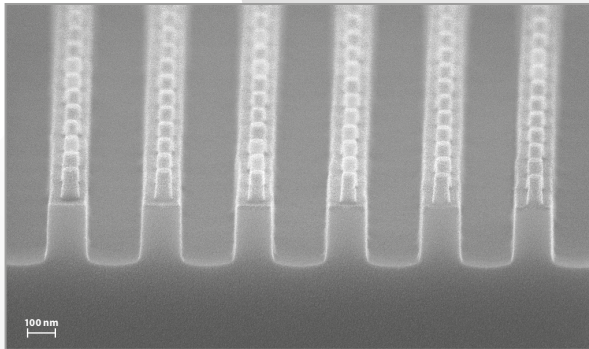


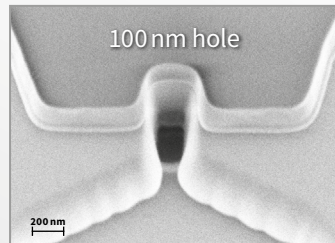
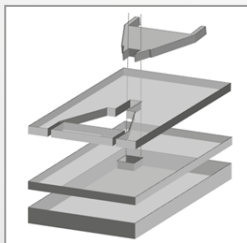
## Multi-layer 3D



3 layer exposures ▶ 8 steps, 5 μm pitch

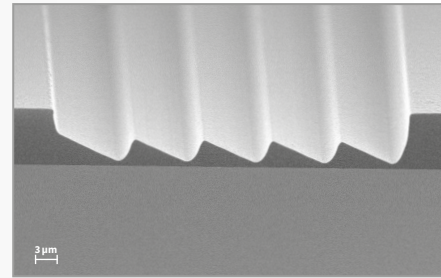


60 nm pillars on 120 nm lines

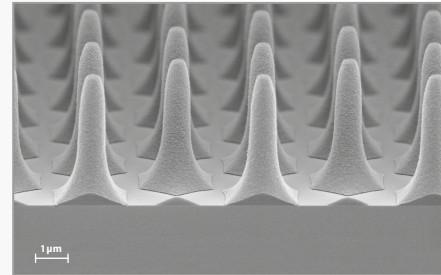


Master for HP self alignment technology

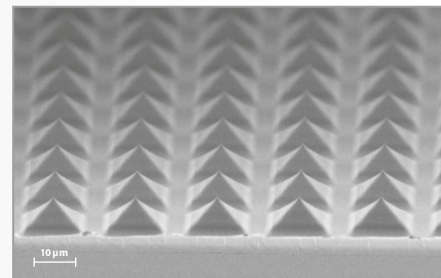
## Analog 3D



10 μm pitch, 4 μm height



3 μm pitch, 4 μm height



20 μm pitch, 10 μm height

## MASTER STAMPS

### Contact



# MASTER STAMPS

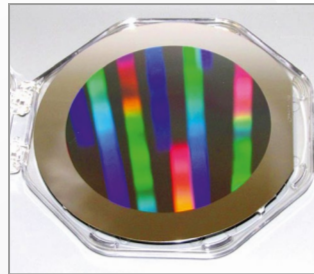
We provide master stamps for any replication techniques and for versatile applications

- **Material:** silicon, quartz, resist
- **Stamp size:** from a few mm<sup>2</sup> up to substrate size
- **Feature types:** binary, multi-level 3D, analog 3D
- Wide range of pattern dimensions from nano-meter- to micrometer-scale
- Optionally, pattern generation on pedestal
- Detailed characterization by in-line measurement tools
- Fabrication in a certified line in an ISO4 clean room

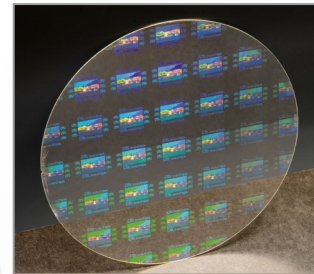
Based on our experience we assist with our customers to identify the most appropriate solution for them



## Substrates

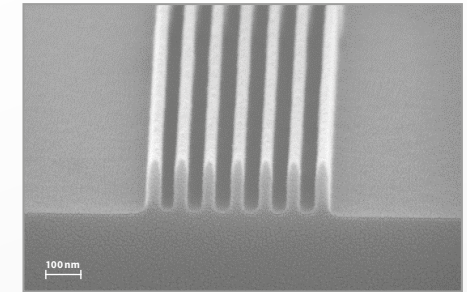


6", 8" Si wafer



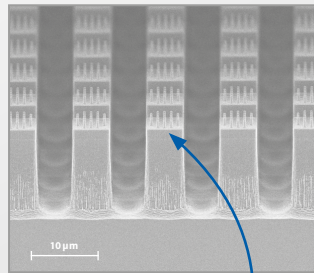
6", 8", 12" Qz wafer

## Binary

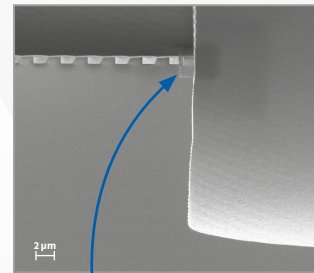


40 nm half pitch

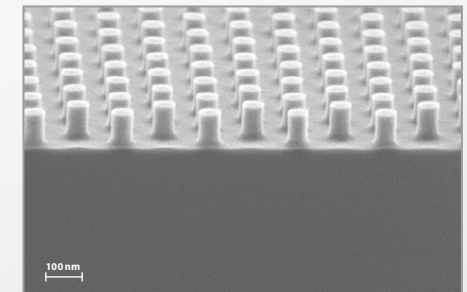
## Mesa: Patterning on Pedestal



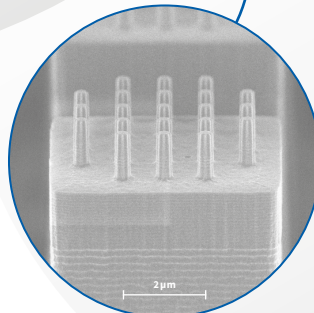
15 μm pedestal



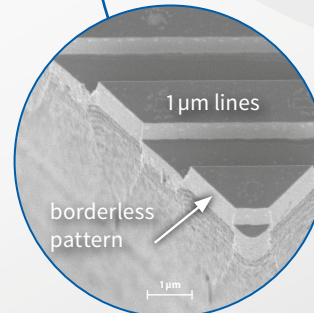
20 μm pedestal



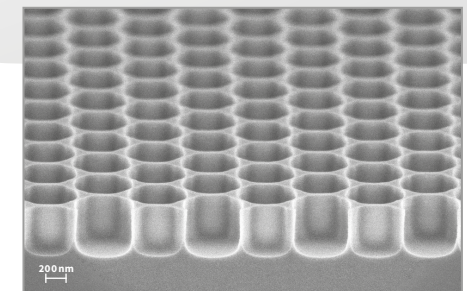
50 nm half pitch



500 nm pillars, 1.5 μm height



borderless patterning on a pedestal



500 nm diameter